



# Justin BD&L

## Business Development & Licensing

### **Justin BD&L, Inc. Head Office**

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### **Justin BD&L, Inc. Clean Room Facility and R&D Center**

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Founded in 2000, Justin BD&L, Inc. has been providing customers with Surplus/Used Semiconductor/LED Manufacturing Equipment, OEM/2<sup>nd</sup> Source Spare Parts and Process Monitoring/Enhancement Kit at a price that will satisfy your reasonable budget in the shortest amount of time.

By serving refurbishment, modification, upgrade (scheduler software and hardware), start-up/installation labor service, relocation (decommission, rigging, crating, shipping) for Front-End/Fabrication, Back-End/Assembly and ATE/Automatic Test Equipment with a business philosophy that pursues the real value of its customers, Justin BD&L, Inc. is now offering customers cost-effective solutions to maintain a competitive place in the Semiconductor/LED Manufacturing/Foundry Industry.

成立于2000年, Justin BD&L, Inc.一直在满足客户合理预算的最短期限内提供二手半导体/LED设备, OEM(原始设备制造商)/替代OEM零组件和工艺监控系统/增强型模块。对于半导体/LED 前后段制程设备(Front-End/FAB, Back-End/Assembly)和ATE/自动测试设备, 提供设备翻新, 改造, 升级(Scheduler软件和硬件), Start-up/安装和调试服务,移机(拆机, 装配, 包装, 运输)服务。 公司的经营哲学理念是为客户追求真正的价值,Justin BD&L, Inc.帮助客户找到最节省价格的解决方案, 因此我们的客户在半导体/LED生产制造/晶圆代工厂业内持续占有竞争之地。

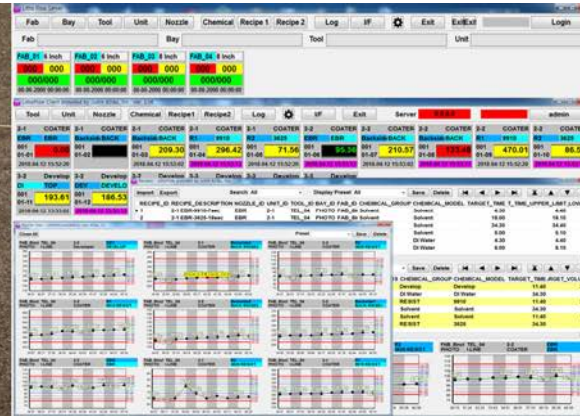
### LithoFlow™ Chemical FMS/Flow Monitoring System

Real Time Monitoring with MAX 75,000 Sensors via Ethernet Connection, Group Monitoring available for Photo-Lithography Process (Photo Resist, SOG/SOD, Solvent, Developer Solution and DI Water, etc.), Wet Etch Process and CMP Process



### LithoFlow™ Chemical FMS/Flow Monitoring System

液体流量监测系统, 通过Ethernet连接, 实时监测最高可达75,000个液体流量监测传感器, 可实现群组监控, 用于光蚀刻技术(光阻剂, SOG旋涂玻璃/SOD旋涂绝缘介质, 溶剂, 显影液和DI Water等), 湿蚀蚀工艺和化学机械研磨工艺



### Surplus/Used Semiconductor/LED Equipment & OEM/2<sup>nd</sup> Source Spare Parts

[http://www.surplushere.com/Inventory/JustinBDnL\\_Inventory.pdf](http://www.surplushere.com/Inventory/JustinBDnL_Inventory.pdf)

### 二手半导体/LED设备和OEM(原始设备制造商)/替代OEM零部件

[http://www.surplushere.com/Inventory/JustinBDnL\\_Inventory.pdf](http://www.surplushere.com/Inventory/JustinBDnL_Inventory.pdf)



Semiconductor Process Monitoring and Enhancement Kit for Lithography, Dry Etch, CVD, Thin Film and Utility/Facility.

用于光蚀刻技术, 干刻蚀, 化学气相沉积, 薄膜和厂务设施的半导体工艺监测系统和增强型模块

**Quality Semiconductor Manufacturing Equipment/Tools and Process Enhancement Solutions/Services for Sale**

Updated on February 11, 2026 (<http://www.surplushere.com>)

No.	Process #1	Process #2	Maker	Model	Description	Wafer Size	Details	Condition
1	Front-End	Lithography	TEL	Clean Track ACT12	Photo Resist Coat and Develop System	12	Single Block, 1C2D1IFB, Left to Right Flow	Excellent
2	Front-End	Lithography	TEL	Clean Track ACT12	Photo Resist Coat and Develop System	12	Single Block, PIQ, 1PCT1PDT, Left to Right Flow	Excellent
3	Front-End	Lithography	TEL	Clean Track ACT12	Interface Unit for Photo Resist Coat and Develop System	12	Interface Unit for TEL Clean Track ACT12, Left to Right Flow	Excellent
4	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Dual Block, 4C4D1IFB, 4PHP, Right to Left Flow, 4SUCs SMIF, ASML PAS5500	Excellent
5	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Dual Block, 4C4D1IFB, 4PHP, Left to Right Flow, 4UNCs, Nikon	Excellent
6	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Dual Block, 3C4D1IFB, 4PHP, Right to Left Flow, 4UNCs, ASML PAS5500	Excellent
7	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Dual Block, 3C4D1IFB, 4PHP, Left to Right Flow, 4UNCs, Canon ES3	Excellent
8	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Single Block, 2C2D1IFB, 4PHP, Left to Right Flow, 3SUCs, Nikon S204B	Excellent
9	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Single Block, 2C2D1IFB, 4PHP, Left to Right Flow, 3SUCs, Nikon NSR2205EX14C	Excellent
10	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Single Block, 2C2D1IFB, 4PHP, Right to Left Flow, 3SUCs, Nikon NSR2205EX14C	Excellent
11	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Single Block, 2C2D1IFB, 4PHP, Right to Left Flow, 3SUCs, Nikon S204B	Excellent
12	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Single Block, 2C2D1IFB, 3PHP, Right to Left Flow, 4UNCs, ASML PAS5500	Excellent
13	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Single Block, 2C2D1IFB, 3PHP, Right to Left Flow, 4UNCs, ASML PAS5500	Excellent
14	Front-End	Lithography	TEL	Clean Track ACT8	Photo Resist Coat and Develop System	8	DUV, Single Block, 2C2D1IFB, 4PHP, Left to Right Flow, 4UNCs, Nikon NSR2205EX14C	Excellent
15	Front-End	Lithography	Justin BD&L	LithoFlow - Group Monitoring Version	LithoFlow Chemical Flow Monitoring System for Multi Tools/Machines Application with real time Remote Monitoring Groupware via Ethernet	N/A	<ol style="list-style-type: none"> <li>Real Time Flow Monitoring with Alarm/Warning and Interlock/Stop</li> <li>Flow Sensor : <ol style="list-style-type: none"> <li>FinFlow Type is available up to Viscosity 50cp (1cc/1sec)</li> <li>Micro MEMS Thermo Sensor : No limit on Viscosity</li> </ol> </li> <li>Multi Tools/Machines Group Monitoring Application via Ethernet <ol style="list-style-type: none"> <li>MAX 75,000 Sensors (MAX 250 Tools, 30,000 Spin Units)</li> <li>MAX 300 Sensors per Tool (MAX 120 Spin Units) with 15 Interface Controller Group (1 Group consists of 1 Main Controller + 1 Add-on Controller)</li> <li>Multi Bands Outputs : Max 4 Upper &amp; 4 Lower Limit "Alarm/Warning" and 1 Upper &amp; 1 Lower Limit "Interlock/Stop"</li> <li>Multi Recipe Support (MAX 20 Recipes per Dispense Nozzle)</li> <li>Interchangeable with TEL OEM Fin Flow Sensor (Clean Track ACT 8 and ACT 12)</li> <li>FDC Option Support Available</li> </ol> </li> <li>Available for Photo Resist, SOG/SOD, Solvent (EBR, Back Rinse, Solvent Bath, Cup Rinse, Nozzle Rinse), Develop Solutions, DIW Top Rinse, etc.</li> <li>Available for All Photo Tracks including TEL Lithius, Lithius Pro, Sokudo, TEL Clean Track Mark 7, Mark 8, ACT 8 or ACT 12 DNS 60A, 60B, 80A, 80B, SK200W, SK2000. SVG 86, 88, 90, 90-S, 90-SE, Tazmo SEMIX SOG Coater</li> </ol>	New
16	Front-End	Lithography	Justin BD&L	LithoFlow - Single Track/Tool Version	LithoFlow Chemical Monitoring System for Single Tool/Machine Application	N/A	<ol style="list-style-type: none"> <li>Process Monitoring with Alarm/Warning and Interlock/Stop</li> <li>Flow Sensor : <ol style="list-style-type: none"> <li>FinFlow Type is available up to Viscosity 50cp (1cc/1sec)</li> </ol> </li> <li>Single Tool/Machine Application <ol style="list-style-type: none"> <li>USB Connection to Laptop</li> <li>MAX 8 Spin Units, 32 Sensors with 4 USB Interface Controllers via 1 USB Hub (4 Ports)</li> <li>1 Band Output : 1 Upper (Alarm/Warning or Interlock/Stop) and 1 Lower (Alarm/Warning or Interlock/Stop) Limit</li> <li>Multi Recipe Support (MAX 20 Recipes per Dispense Nozzle)</li> <li>Interchangeable with TEL OEM Fin Flow Sensor (Clean Track ACT 8 and ACT 12)</li> <li>FDC Option Support Available</li> </ol> </li> <li>Chemical : Same as Multi Tools/Machines Version</li> <li>Available for All Photo Tracks : Same as Multi Tools/Machines Version</li> </ol>	New
17	Front-End	Lithography	TEL	Clean Track Mark8	Photo Resist Coat and Develop System	8	Single Block, 2C2D1IFB, Right to Left Flow	Excellent
18	Front-End	Lithography	TEL	Clean Track Mark8	Photo Resist Coat and Develop System	8	Single Block, 2C2D1IFB, Right to Left Flow	Excellent
19	Front-End	Lithography	TEL	Clean Track Mark8	Photo Resist Coat and Develop System	8	Single Block, 2C1D, Left to Right Flow	Excellent

**Quality Semiconductor Manufacturing Equipment/Tools and Process Enhancement Solutions/Services for Sale**

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No.	Process #1	Process #2	Maker	Model	Description	Wafer Size	Details	Condition
20	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Dual Block, 2C3D1IFB, Right to Left Flow	Excellent
21	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Dual Block, 2C3D, Right to Left Flow	Excellent
22	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Dual Block, 2C3D, Left to Right Flow	Excellent
23	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Dual Block, 5D, Left to Right Flow	Excellent
24	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Coat and Develop System	8	Single Block, 2C2D1IFB, Left to Right Flow	Excellent
25	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Coat and Develop System	8	Single Block, 2C2D1IFB, Left to Right Flow	Excellent
26	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Coat and Develop System	8	Single Block, 2C2D1IFB, Left to Right Flow	Excellent
27	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Coat and Develop System	8	Single Block, 2C2D1IFB, Left to Right Flow	Excellent
28	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Coat and Develop System	8	Single Block, 2C2D1IFB, Left to Right Flow	Excellent
29	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Coat and Develop System	8	Single Block, 2C2D1IFB, Left to Right Flow	Excellent
30	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Coat and Develop System	8	Single Block, 2C2D, Right to Left Flow	Excellent
31	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 3D, Right to Left Flow	Excellent
32	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 3D, Right to Left Flow	Excellent
33	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 3D, Right to Left Flow	Excellent
34	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 3D, Left to Right Flow	Excellent
35	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 3D, Right to Left Flow	Good
36	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 3D, Right to Left Flow	Good
37	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 3D, Left to Right Flow	Good
38	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 3D, Right to Left Flow	Some Parts Missing
39	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Coat System	8	Single Block, 3C (PIQ/Polyimide Coat)	Some Parts Missing
40	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 2D1RSV, Right to Left Flow	Some Parts Missing
41	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 2D1RSV, Left to Right Flow	Some Parts Missing
42	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 1C2D1SCR, Right to Left Flow	Some Parts Missing
43	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 2SCR1RSV, Left to Right Flow	Some Parts Missing
44	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 2SCR1RSV, Left to Right Flow	Some Parts Missing
45	Front-End	Lithography	TEL	Clean Track Mark7	Photo Resist Develop System	8	Single Block, 2SCR1RSV, Right to Left Flow	Some Parts Missing
46	Front-End	Lithography	DNS	SK-W80B-AVPE	Photo Resist Coat and Develop System	8	1C2D1IFB, Right to Left Flow	Excellent
47	Front-End	Lithography	DNS	SK-80BW-AVPE	Photo Resist Develop System	8	1C2D	Some Parts Missing
48	Front-End	Lithography	DNS	SKW-80A-BVPE	Photo Resist Coat and Develop System	8	1RSV1C2D1IFB	Excellent
49	Front-End	Lithography	DNS	SKW-80A-BVPE	Photo Resist Coat and Develop System	8	1RSV1C2D1IFB	Excellent
50	Front-End	Lithography	ASML	PA5500/300C	Lens Unit, Cables and Panels only	8	Lens Unit, Cables and Panels only	
51	Front-End	Metrology	Nicolet	ECO-1000S	FT-IR	8	FT-IR	Controller Missing
52	Front-End	Metrology	SDI	SPV-1050	Contamination Monitoring System	8	Contamination Monitoring System	Excellent
53	Front-End	Metrology	Asyst	Spartan	EFEM Wafer Sorter	12	2 FOUP, 300mm EFEM Wafer Sorter	Excellent
54	Front-End	Metrology	Asyst	PST100	Wafer Sorter	8	SMIF, WMS/Wafer Metrology Sorter (2SMIF Indexers)	Upgraded, Operational
55	Front-End	Metrology	Asyst	PST100	Wafer Sorter	8	SMIF, WMS/Wafer Metrology Sorter (2SMIF Indexers)	Upgraded, Operational
56	Front-End	Clean	DNS	SS-W80A-AR	Wafer Spin Scrubbing/Cleaning	8	2 Front, 2 Back Side Scrubbing Units w/ Nanospray	Excellent
57	Front-End	Clean	DNS	SS-W80A-AR	Wafer Spin Scrubbing/Cleaning	8	2 Front, 2 Back Side Scrubbing Units w/ High Pressure Jet	Excellent
58	Front-End	Clean	DNS	SS-W80A-AR	Wafer Spin Scrubbing/Cleaning	8	3 Back Side Scrubbing Units w/ High Pressure Jet	Excellent
59	Front-End	Clean	DNS	SS-W80A-AR	Wafer Spin Scrubbing/Cleaning	8	4 Front Side Scrubbing Units w/ Nanospray	Excellent
60	Front-End	Clean	DNS	SS-W80A-AR	Wafer Spin Scrubbing/Cleaning	8	4 Front Side Scrubbing Units w/ High Pressure Jet	Excellent

**Quality Semiconductor Manufacturing Equipment/Tools and Process Enhancement Solutions/Services for Sale**

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No.	Process #1	Process #2	Maker	Model	Description	Wafer Size	Details	Condition
61	Front-End	Clean	DNS	SS-W80A-AR	Wafer Spin Scrubbing/Cleaning	8	Upgrade and Remanufacturing Compatible Technology Service with New Industrial Controller and Digital I/O Controller including Windows GUI scheduler SW, WPH upgraded, New Spin Motor/Driver and New Servo Motor/Driver for INR & WTR Robots Wafer Level Recipe Processing and Command, Real Time Process Log Online Communication (SECS/GEM) Option with real time wafer & lot tracking Inch Conversion (4/5/6/8") for both Silicon Wafer and LED Sapphire Substrate	Remanufactured/ Upgraded/ Operational
		Clean	DNS	SS-W80A-AR	Wafer Spin Scrubbing/Cleaning	4/5/6/8	Upgraded DNS SS-W80A-AR Wafer Spin Scrubber - 3 Front, 3 Back Side Scrubbing Units w/ Nanospray - Spin Scrubbing Method Modification (High Pressure Jet, D-Sonic, Nanospray) - Spin Unit Modification (Front Side, Back Side, Double Sides) - Wafer Flow Modification (Left to Right or Right to Left) - Note : HF, NH4OH, SC1 or SC2 Chemical Scrubbing Modification is available	
		Lithography /CVD	DNS	SC-W80A-AVFG	SOG Coat and Vertical Furnace System	4/5/6/8	Upgraded DNS SC-W80A-AVFG SOG Coat and Vertical Furnace - 2 SOG Coat Units and 1 Vertical Furnace	
62	Front-End	Etch	AMAT	DPS II	Metal Etch	12	3 DPS II Metal Etch Chs, 2 Axiom Chs, Vintage 2008	Excellent
63	Front-End	Etch	Lam Research	Autoetch 490	Single Chamber Poly Etch	8	Single Chamber Poly Etcher	
64	Front-End	Ash	Novellus-Gasonics	A3010	Dry Ash	8	Single Chamber Dry Asher	Operational
65	Front-End	CVD	AMAT	P5000	SA BPSG	8	3 SA BPSG Chambers (TEOS, PLIS)	Good
66	Front-End	Ion Implant	Axcelis-Eaton	GSD100	Gyro Disk for GSD100	8	Gyro Disk for GSD100	Overhauled
67	Front-End	RTP	Mattson	AST3000	RTP	8	Single Chamber RTP with 3 Load/unloaders	Power-up, Initialized
68	ATE	EDS	TEL	P-12XL	Automatic Wafer Prober/Probe Station	12	Automatic Wafer Prober/Probe Station	Power-up, Initialized
69	ATE	EDS	TEL	P-12XL	Automatic Wafer Prober/Probe Station	12	Automatic Wafer Prober/Probe Station	Power-up, Initialized
70	ATE	EDS	Accretech-TSK	MHF300L	Manipulator of Automatic Wafer Prober/Probe Station	8	MHF300L, Manipulator of Automatic Wafer Prober/Probe Station	Operational
71	ATE	EDS	Accretech-TSK	MHF300L	Manipulator of Automatic Wafer Prober/Probe Station	8	MHF300L, Manipulator of Automatic Wafer Prober/Probe Station	Operational
72	ATE	EDS	ESI	9275	Laser Repair System - Modules and Parts only	8	Laser Repair System - Modules and Parts only	Modules and Parts only
73	Back-End	Saw	Disco	N/A	Heavy Smoker for Disco Dicing Saw DFD6361	N/A	Heavy Smoker for Disco Dicing Saw DFD6361, Vintage 2006	Power-up, Initialized
74	Back-End	Saw	NGK	Maggon II	CO2 Bubbler, NGK Maggon II, RCII-2000ACD-S	N/A	CO2 Bubbler, NGK Maggon II, RCII-2000ACD-S for Disco DFD6361, Vintage 2006	Power-up, Initialized
75	Back-End	Saw	Disco	DSC141	After Sawing Cleaner - Spin/Rinse/Dryer	8	Automatic Spin/Rinse/Drying System after Sawing, Vintage 2006	Power-up, Initialized
76	Back-End	Detape	Lintec	RAD2000/F8	UV Irradiator for Detaping System	8	Automatic UV Irradiator for Detaping System	Good
77	Back-End	Tape	Nitto	DR8500II	Automatic Taper	8	Automatic Laminator/Taper	Some Parts Missing
78	Back-End	Tape	Nitto	DR8500II	Automatic Taper	8	Automatic Laminator/Taper	Some Parts Missing
79	Back-End	Detape	Nitto	HR8500II	Automatic Detaper, Tape Remover	8	Automatic Detaping System, Detaper, Tape Remover with UV Module	Power-up, Initialized
80	Back-End	Detape	Nitto	HR8500II	Automatic Detaper, Tape Remover	8	Automatic Detaping System, Detaper, Tape Remover without UV Module	NEL Touch Panel missing
81	Back-End	Detape	Takatori	ATM8100	Automatic Detaper, Tape Remover	8	Automatic Laminator/Taper	Good
82	Back-End	Detape	Takatori	ATRM2100	Automatic Detaper, Tape Remover	8	Automatic Detaping System, Detaper, Tape Remover	Excellent
83	Auxiliary	Vacuum Pump	Various	Various	Dry Pump and Roughing Pump	N/A	Edwards iH600, iH80, iGX100M, iQDP80, QDP80, iQDP40, QDP40 Edwards iQDP80+QMB500, iQDP80+QMB250, QDP80+QMB500 Ebara A150W-T, A70W, A30W, 80x25, 40x20 Alcatel ADS501, Leybold WSU501, Kashiyama SD90V	
84	Auxiliary	TMP	Edwards	Various	Seiko-Seiki TMP/Turbo Modular Pump and Controller	N/A	TMP/Turbo Modular Pump and Controller	
85	Auxiliary	Compressor	CTI	8510, 8500	Cryo Compressor	N/A	Cryo Compressor	
86	Auxiliary	RF Generator	Various	Various	RF Generator or RF Power Supply	N/A	RF Generator or RF Power Supply - AE/Advanced Energy, Daihen, Adtec	
87	Auxiliary	RF Match	Various	Various	RF Match	N/A	RF Match - AE/Advanced Energy, Daihen	



# Justin BD&L

## Business Development & Licensing

**surplushere.com**  
services provided by Justin BD&L, Inc.

- Advanced Solutions Provider for Semiconductor and LED Manufacturing Equipment**
- + Windows GUI Scheduler Software Solutions for Semiconductor Manufacturing Equipment
  - + Process Monitoring and Performance Enhancement Products and Solutions
  - + Used and Refurbished Equipment for Sale
  - + Refurbishment, Modification, Engineering and Labor Service



### Clean Room Facility I

- **The State of the Art Clean Room Facility for Quality Refurbishment Service in New Dongtan II City**  
5min driving distance from Samsung FABs, 30min from Seoul and 90min from Incheon International Airport  
Main Building Size : 1,676.03m<sup>2</sup> / 18,040.23ft<sup>2</sup> / 507pyung  
Clean Room (Class 100) Size : 552.63m<sup>2</sup> / 6,013.41ft<sup>2</sup> / 169pyung  
Clean Room (Class 1,000) Size : 2,079.35m<sup>2</sup> / 22,391.14ft<sup>2</sup> / 629pyung
- All Clean Rooms have DI Water, PCW, CDA, Power (480kW, 220VAC)
- On-site Solar Power Generation Systems installed for Green Energy

### Clean Room Facility II

- 2nd Facility (3 Floors) completed in Mar 2007 (2,622.76 m<sup>2</sup> / 28,230.89 ft<sup>2</sup> / 793pyung)  
- 5min driving distance from Samsung FABs, 30min from Seoul and 90min from Incheon International Airport
- The State of the Art Clean Room Facility for the Quality Refurbishment Service of 200mm (8"), 300mm (12") and 450mm (18") Wafer FAB Tools
- All Clean Rooms have DI Water, PCW, CDA, Power (480kW, 220VAC)
- On-site Solar Power Generation Systems installed for Green Energy



## Clean Room Facility and R&D Center

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